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Application of nanoscratching in electronic devices

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Abstract

The lithography is a basic operation in the fabrication process of semiconductor devices. The scaling ability is the reason why the atomic force microscopy (AFM) nanolithography is currently studied in many laboratories. In the paper, the results of the mechanical AFM lithography, named nanoscribing or nanoscratching, are presented. In this method, the pattern is created by mechanical interaction between the AFM tip and a sample. This interaction requires the application of large forces in microneutons scale.



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